## Applicant(s)/Patent Under Reexamination 09/912,398 **INANAMI ET AL.** Notice of References Cited Examiner Art Unit Page 1 of 1 Thomas H. Stevens 2123

Application/Control No.

## **U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-6,090,528	07-2000	Gordon et al.	430/296
	В	US-6,363,488	03-2002	Ginter et al.	713/201
	С	US-6,578,174	06-2003	Zizzo, Claudio	716/1
	D	US-5,663,891	09-1997	Bamji et al.	716/2
	Ε	US-5,971,585	10-1999	Dangat et al.	700/102
	F	US-5,539,652	07-1996	Tegethoff, Mauro V.	703/14
	G	US-5,512,765	04-1996	Gaverick, Timothy L.	257/202
	Н	US-5,629,845	05-1997	Liniger, Werner	700/67
	1	US-6,560,768	05-2003	Inanami et al.	716/21
	J	US-5,341,302	08-1994	Connors et al.	700/102
	к	US-4,310,743	01-1982	Seliger, Robert L.	219/121.12
	L	US-6,801,881	10-2004	Shah, Sunil C.	703/2
	М	US-			

## **FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	z			-		
	0					
	Р					
	Q					
	R					
	S					
	Т					

## **NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	υ	Pfeiffer-H.C., "Electron Beam Lithography: A Key to VLSI" IEEE N.Y., N.Y., pg. 186 CPP Conference Paper.
	٧	
	w	
	x	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.